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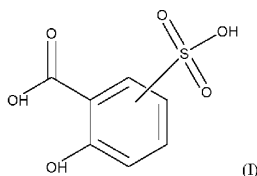
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(54) Title: PHOTORESIST REMOVER COMPOSITIONS



(57) Abstract: The present invention relates to a composition including at least one sulfosalicylic acid having structure (I), or its hydrate, and mixtures thereof and a sulfosalicylic acid having structure (I), or its hydrate, a primary solvent selected from acetone, and methyl ethyl ketone, or a mixture of these solvents, an optionally a secondary solvent which is a glycolic derivative, or a mixture of at least two glycolic derivatives, and an optional surfactant.

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